UV조사 폴리이미드실록산막의 기체투과특성

<u>한두원</u>, 박호범, 이영무 한양대학교 응용화학공학부

Gas Permeation Properties of UV-irradiated Poly(imide siloxane) Membrane

Doo Won Han, Ho Bum Park, Young Moo Lee

National Research Laboratory for Membrane, School of Chemical Engineering, College of Engineering, Hanyang University, Seoul 133-791, Korea

Some of the most interesting and unique features of siloxane containing copolymers are associated with their surface morphology and the resultant surface properties, which distinguish them from other polymeric systems. Due to their very large molar volumes jointed with low intramolecular interactions and high polydimethylsiloxane (PDMS) have very low surface tension and surface energies. As a result, the air-polymer interfaces of siloxane containing copolymers such as poly(imide siloxane) and poly(amideimide siloxane), as well as their blends with other polymers are substantially enriched in the lower surface energy siloxane. The thermodynamic driving force behind this process is the minimization of the interfacial and/or surface energy. It is well known that the surface energy interfacial tensions vary with both temperature and molecular weight of the active probably to some extent with component the copolymer architecture.

Siloxanes are also very well known for their high gas permeabilities. However, siloxane homopolymers are mechanically weak and also do not show high selectivities towards different gases. Siloxane copolymers on the other hand, usually possess good mechanical strength. Through careful selection and design of the

organic backbone structures, it is also possible to improve the gas selectivity of these polymers.

Whereas SiO_x films are versatile materials offering a myriad of applications due to their interesting properties. Their high resistance to oxygen and wafer, and high gas selectivity lead to their use as moisture barriers, protective layers, and gas separation membranes. Usually, techniques used to produce SiO_2 thin films involve restrictive atmospheric conditions. Pyrolytic degradation of polydimethylsiloxane (PDMS) can result in high-quality silicon oxide films at temperatures above 400° C. In addition, PDMS can be converted to SiO_x by exposure to UV light in the presence of atmospheric oxygen at ambient conditions. Simiultaneouly, ozone, an active oxidizing agent, is generated in situ from atmospheric oxygen by exposure to UV light.

In this study, we focused on the change of PDMS phase in the poly(imide siloxane) by UV irradiation. Fig. 1 showed Si_{2p} XPS spectra for the poly(imide siloxane) films before and after exposure to UV for 1 hr. After exposure to UV, the Si_{2p} binding energy shifts toward that of amorphous SiO_2 or to a value corresponding to tetrahedral coordination

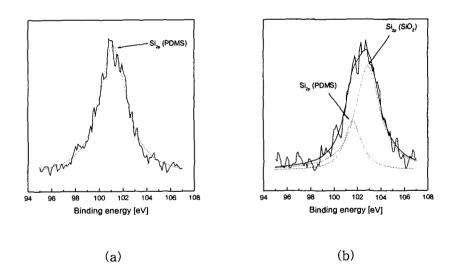


Fig. 1. Si_{2p} XPS spectra for the poly(imide siloxane) films before (a) and after (b) exposure to UV for 60min.

of each silicon atom to four oxygen. Consequently, UV irradiation of poly(imide siloxane) can lead to an organic-inoragnic composite membrane composed of imide domain and converted SiO_2 domain. Particularly, in present work, it would be intensively investigated whether the converted SiO_2 phase in the poly(imide siloxane) film would affect the gas permeation properties through the membrane or not.

Reference

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